

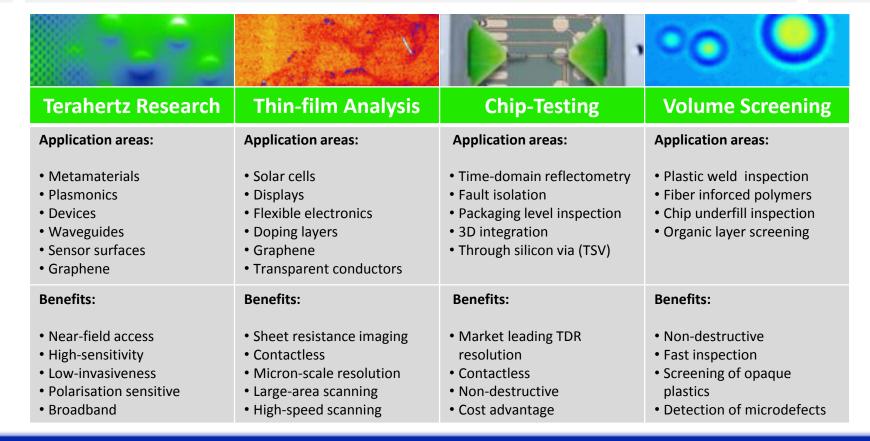
World of Photonics, Laser 2015, Munich

Protemics GmbH Aachen, Germany



Terahertz microprobing technology:

Taking advantage of Terahertz range benefits without being compromised by wavelength-based resolution limitations.



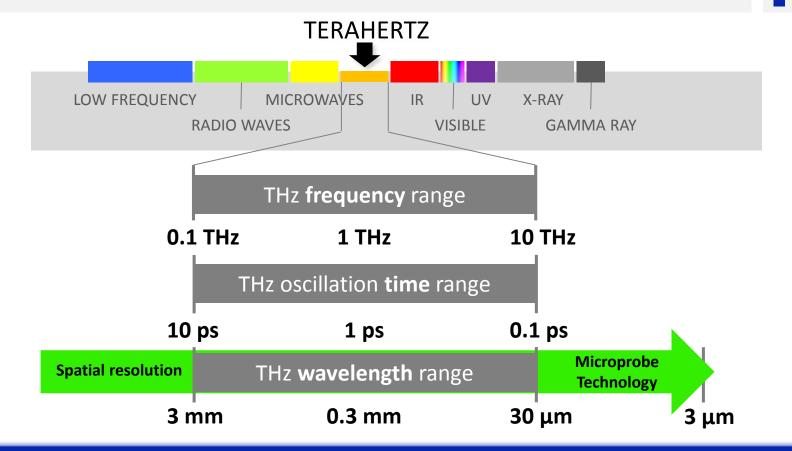


Outline

- Introduction
 - Mismatch between THz radiation wavelengths and micro/nanostructure size
- THz microprobes
 - Working principle
- Thin-film analysis with sub-wavelength resolution on large areas
 - Thin-film conductors (Metals, Graphene, Semiconductors, ITO and ITO-replacement materials)
- THz Metamaterials
 - THz-Metamaterials, Metamaterial-based sensing
- Plastic laser weld inspection
 - Near-field detection of micro-defects
- THz device analysis
 - THz on-chip device characterization
 - Failure localization in chip packages



Introduction





Introduction

Large THz wavelengths are problematic:

- When structures under test are too small (similar to λ or even smaller)
 - Lateral Micro/Nanostructures (Solar cells, electronic structures, micro defects, ...)
 - Only minute (pl) sample volumes available (-> biosensing)
- On signal transfer to or from THz field confining structures
 - Waveguides
 - Integrated devices

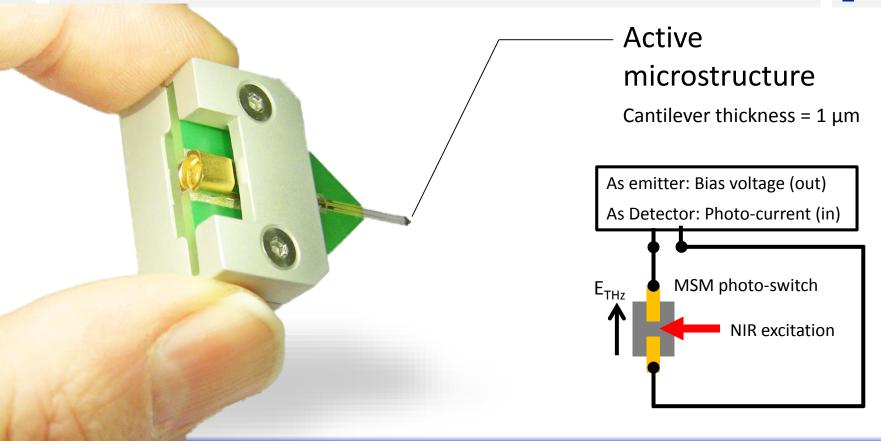
Solution:

- Make THz emitter and/or detector smaller than the wavelength
- Bring the miniaturized emitter/detector in sub-wavelength distance to structure under test

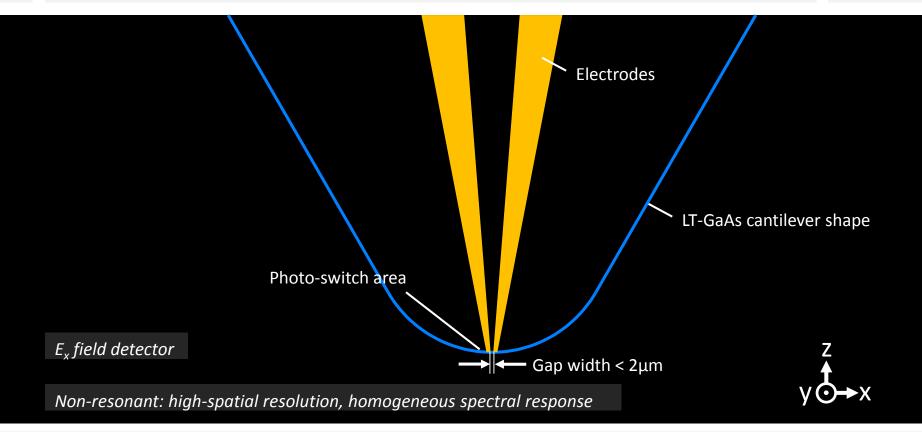


Ultra-fast photoconductive

THz micro-emitters/detectors



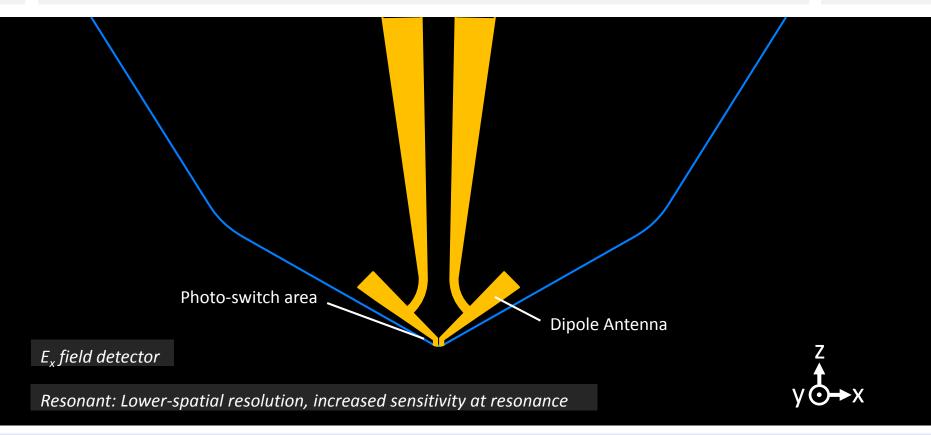
Application specific designs





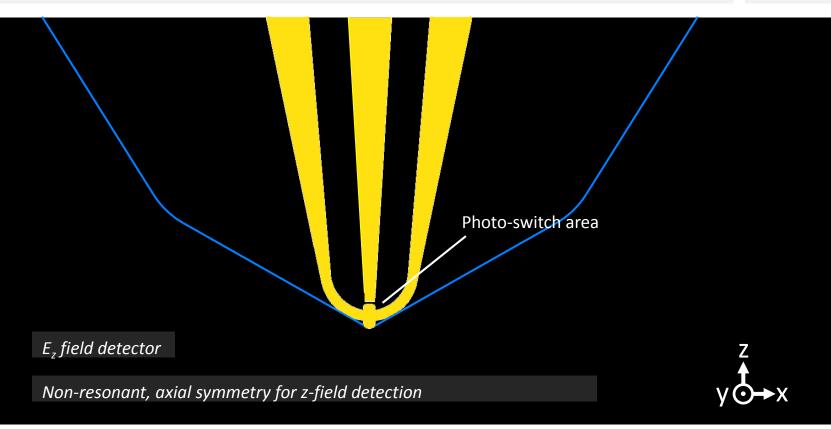
THz microprobes

Application specific designs



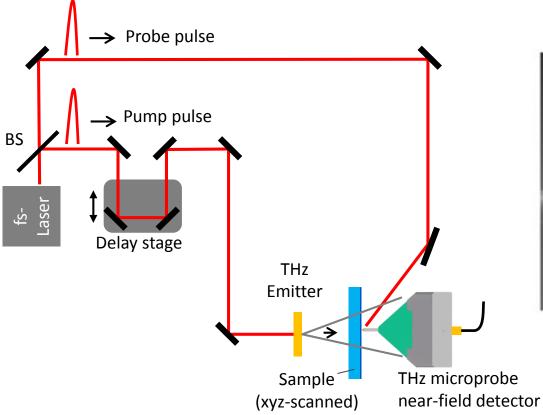


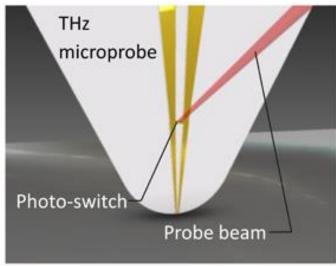
Application specific designs





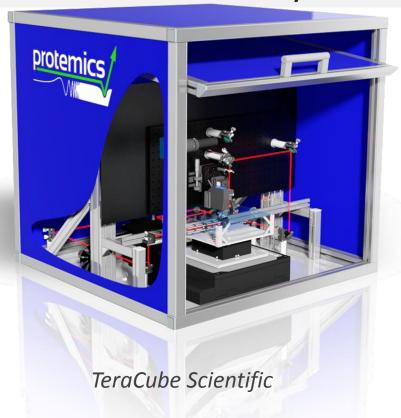
TD near-field sampling







TD near-field system



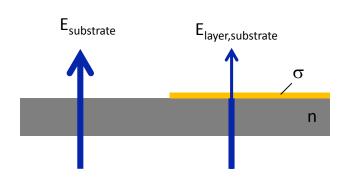
Automated table-top system

- 90x90x90 cm box including:
 - Laser
 - Scanning components
 - Opto-mechanics
 - Optics
 - Electronics
- External components
 - PC
 - Supply unit





- Sheet resistance imaging of thin-film conductors such as
 - Metals
 - Graphene
 - Doped semiconductors
 - Optically transparent conductors: ITO and ITO-replacement materials



Tinkham Formula:
$$\frac{E_{layer,substrate}(\omega)}{E_{substrate}(\omega)} = \frac{1+n}{1+n+Z_0\sigma(\omega)d}$$

Accessible sheet resistance range: 0.1 – 10000 Ohm



Short-comings of state-of-the-art sheet-resistance measurement tools

Contact-based four-point probe measurements are problematic:

- On large-bandgap semiconductors (e.g. GaN or SiC)
 - -> Imprecise measurements because of nonlinear contacts
- On passivated samples (e.g. Solar cells)
 - -> No contact
- On **nanostructures** (e.g. metal mesh nanostructures)
 - -> Requires formation of additional contact pads
- If measurement time matters
 - -> Extremely time-consuming (5s/measurement point)
- If non-**destructive**ness matters
 - -> Puncturing from contact needles



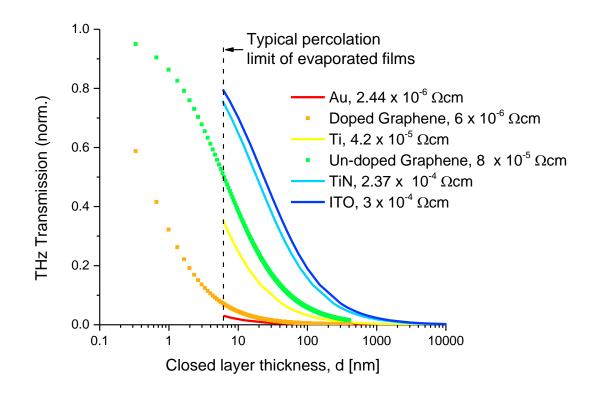


Short-comings of the state-of-the-art sheet-resistance measurement tools

Non-contact Eddy current measurements:

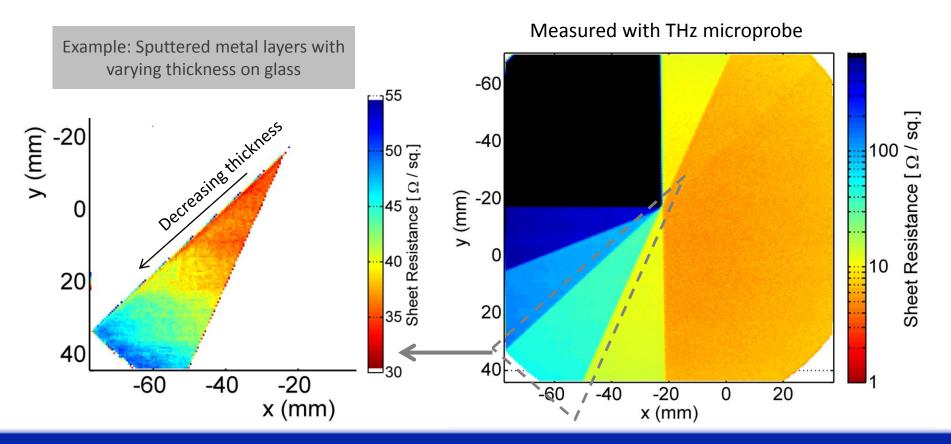
- Spatial resolution is limited to 1 cm for **quantitative** measurements
- Spatial resolution is limited to 2 mm for **qualitative** measurements.





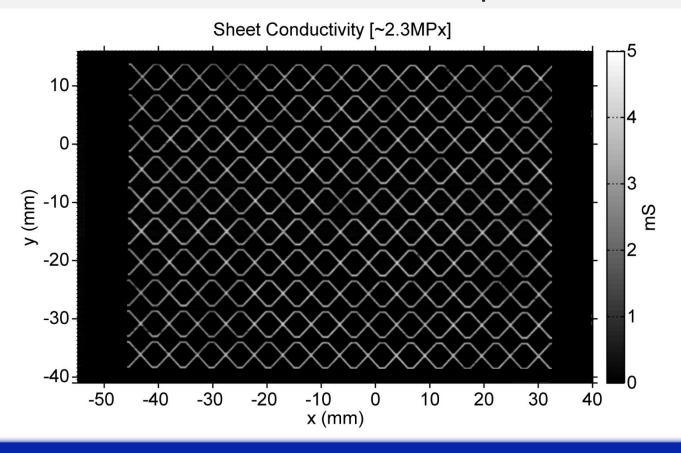
Substrate: Silicon





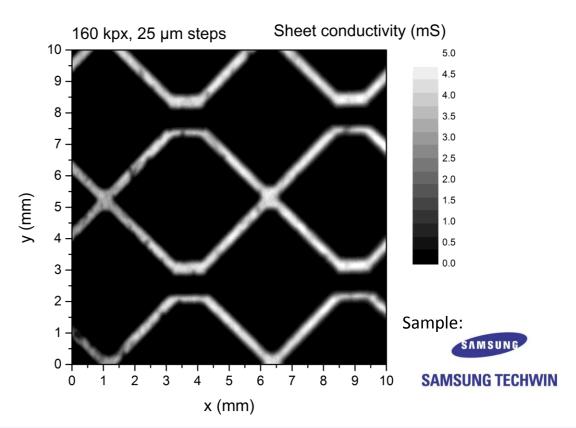


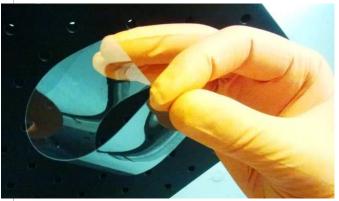
Thin-film conductors: Graphene





Thin-film conductors: Graphene



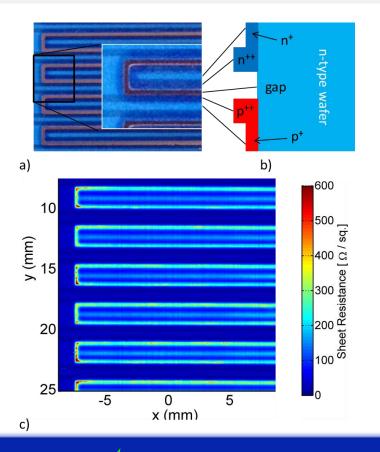


- Graphene pattern on PET foil
- Flexible display application

High-speed contactless raster scanning on **bended** surfaces



Thin-film conductors: Doped mc-Si



- IBC solar cell structure
- Laser-based material ablation process
- Sheet resistance image reveals areas of process induced inhomogenuity
- Applicable on full cell area and textured surfaces

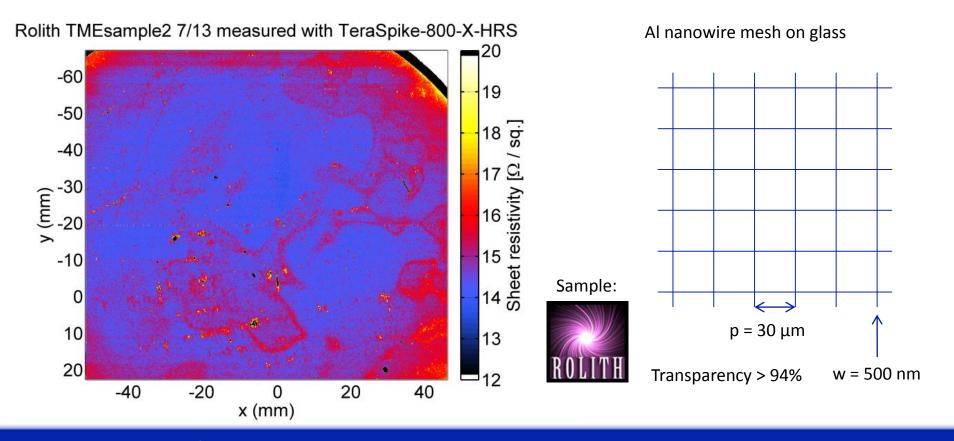
In collaboration with:



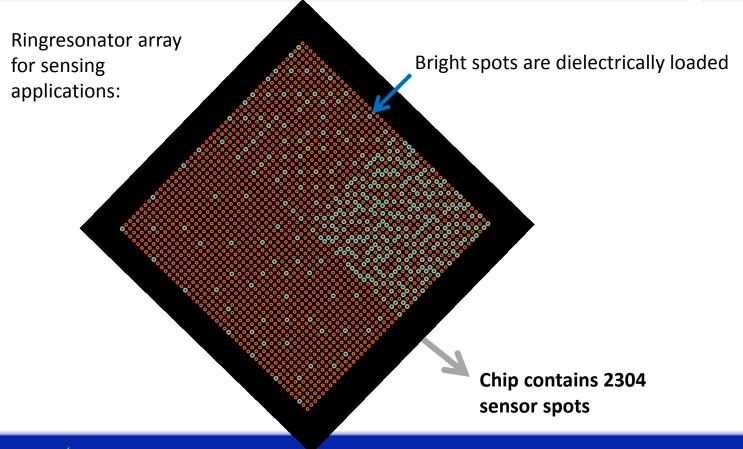


Thin-film conductors: ITO-replacements

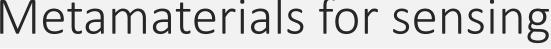


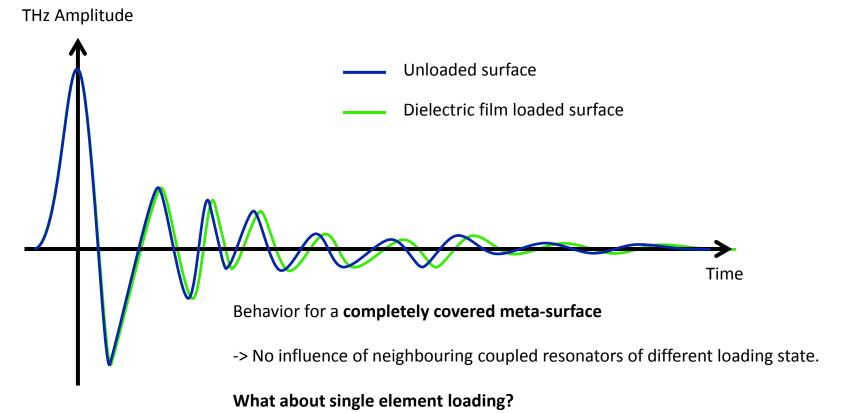




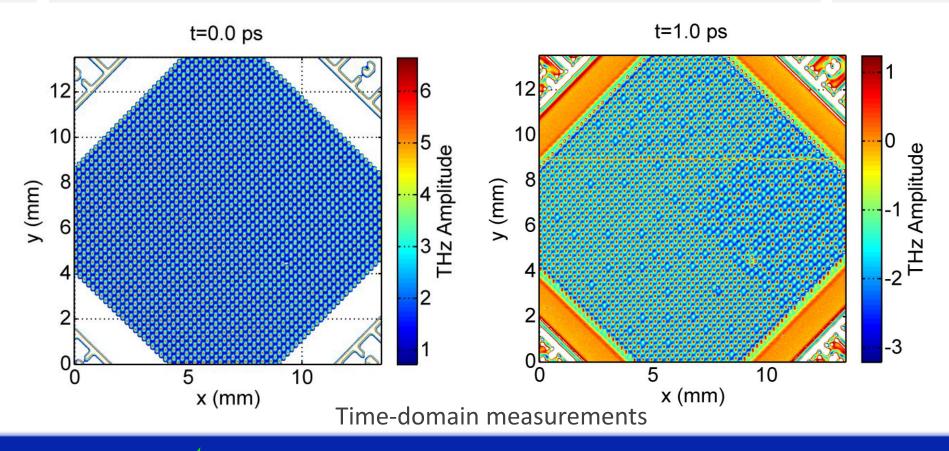




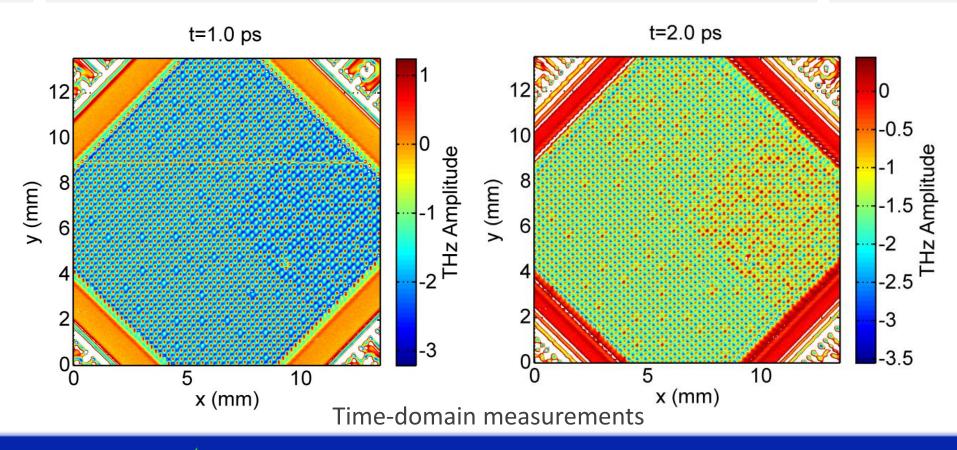




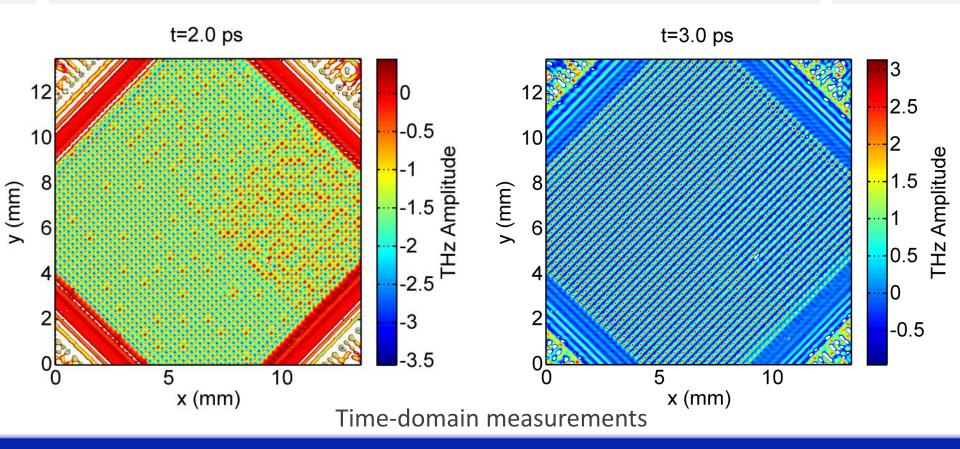




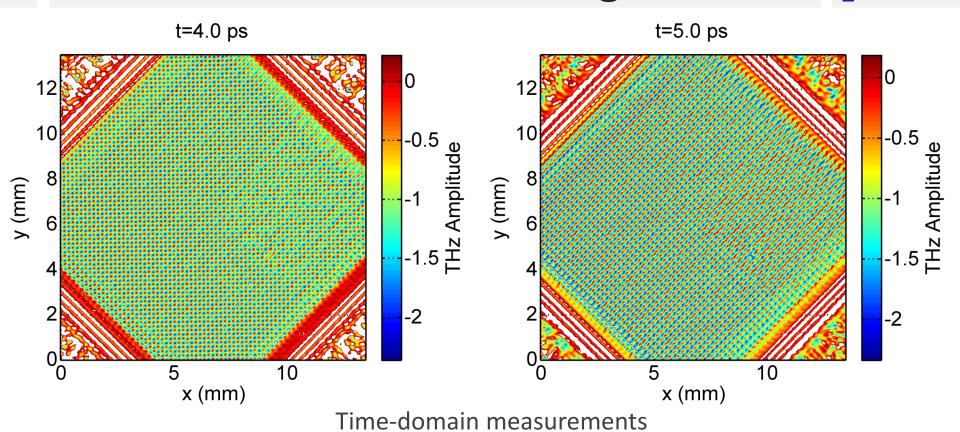








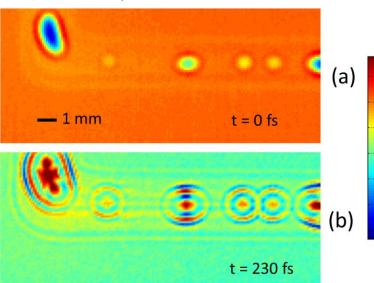


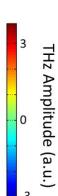


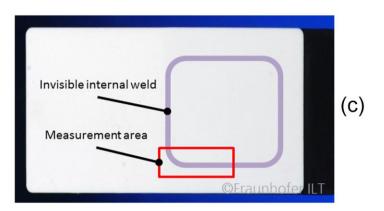


Laser plastic weld inspection

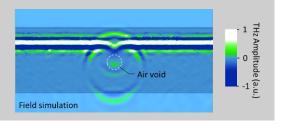
THz microprobe measurement data





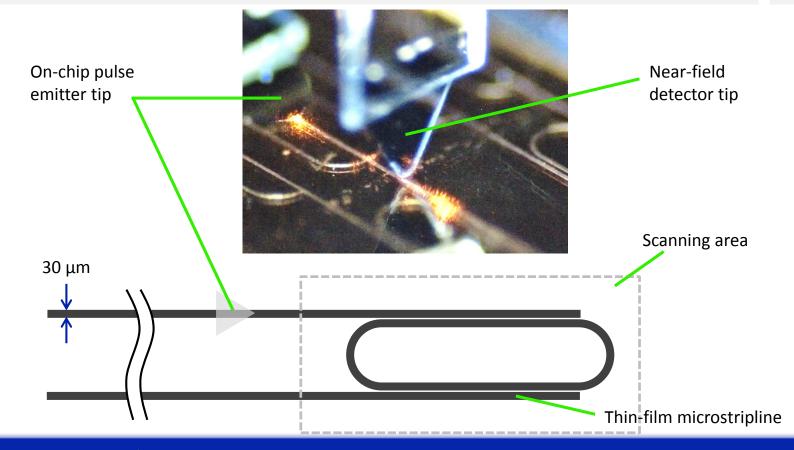


Small objects become visible by scattering light in the near-field:

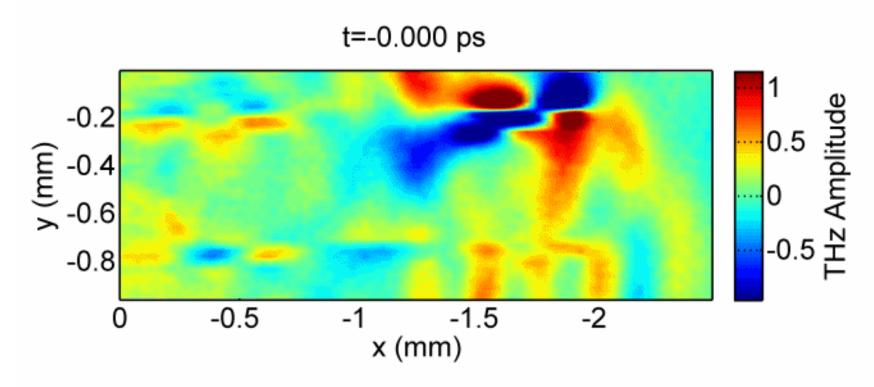




THz on-chip analysis



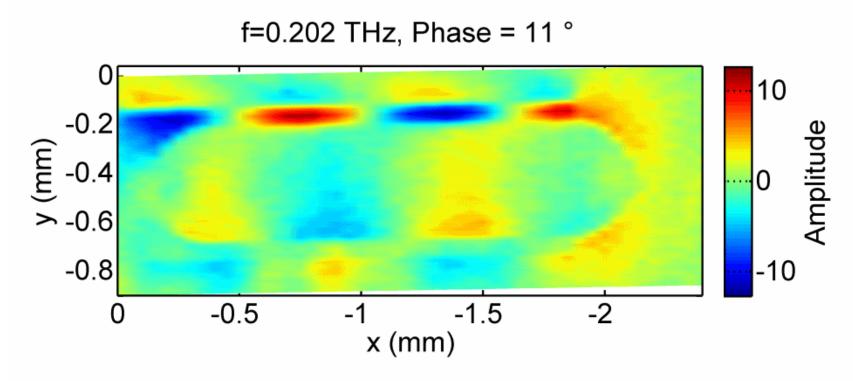
THz on-chip analysis



Time-domain measurement



THz on-chip analysis



Frequency-domain measurement data extraction





Failure localization Target preparation

Failure analysis

Material characterization

(non-destructive)

LIT, TDR, X-ray, ...

(destructive)

Laser, FIB, RIE, wet chemistry, milling, abrasive blasting, ...

(image defect & physical analysis)
SEM / EBSD, EDX,

TEM, ToF-SIMS...

Image correlation, ESPI, ...

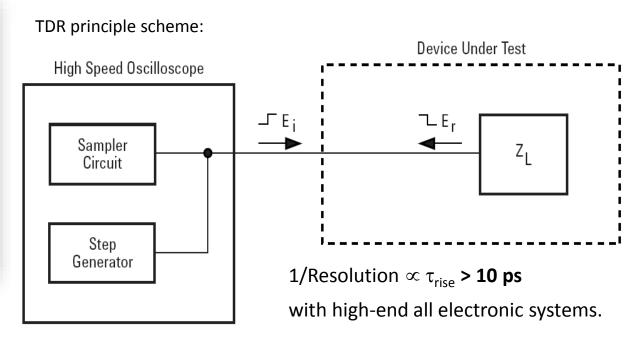
Limited accuracy/information but fast

Expensive & time consuming



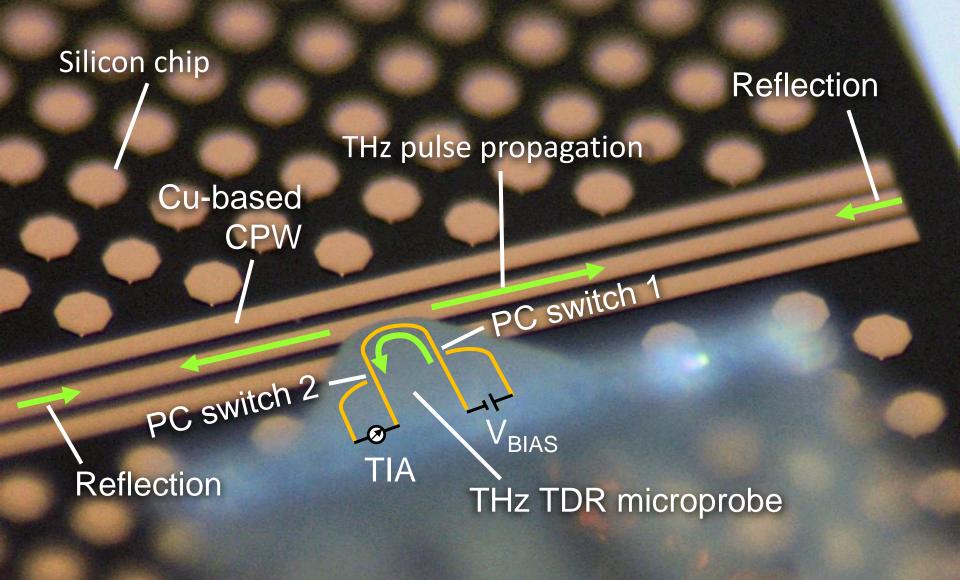


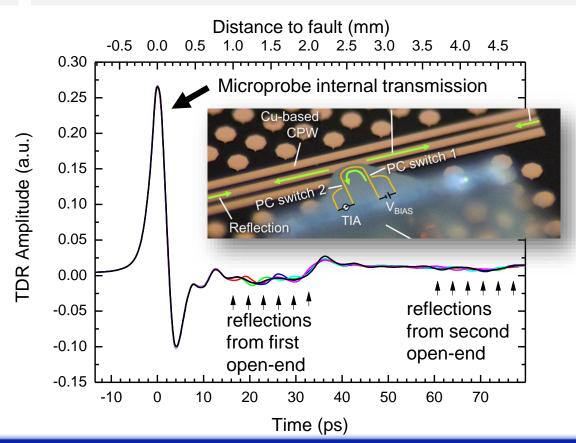
Hewlett-Packard Journal, "Time domain reflectometry" June 1969, Vol. 20, No. 10



Our Terahertz microprobes achieve up to sub-1 ps rise-times!

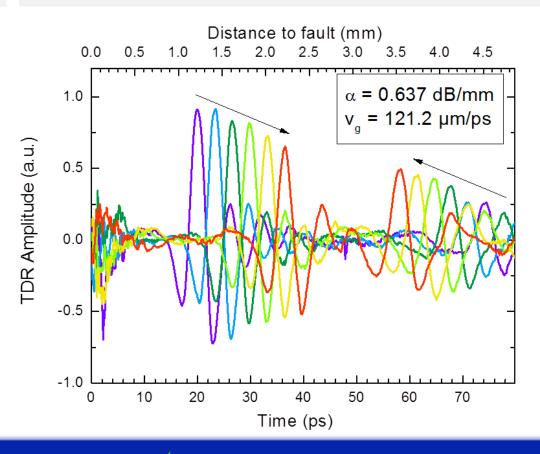






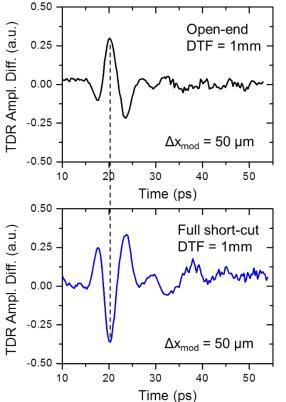
- Internal transmission as reference signal
- Multiple transient scans at different distances to fault
- Reflection signals from short and far distance opens

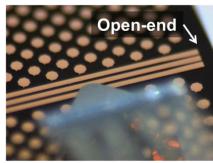


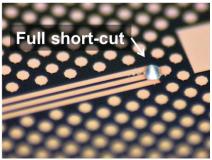


- Suppression of internal transmission signal through distance-to-fault modulation
- Determination of propagation dynamics:
 - Attenuation
 - Group/phase velocities



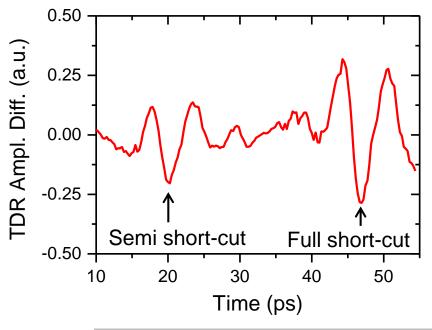


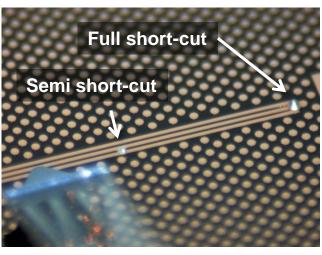




- Type of fault discremination
- Open vs. Short-cut
- Resistive faults
- Resonant faults







Detection of consecutive faults

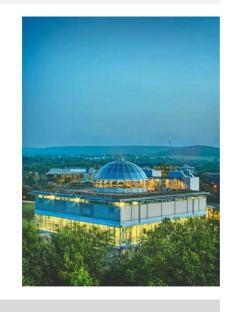
Conclusion

- THz microprobes
 - Efficient and versatile tools to avoid inefficient coupling of free-space THz radiation to micro/nanostructures
- Examples: Surface analysis
 - Sheet resistance imaging
 - Non-destructive (contactless), Fast (< 5ms/Pixel)
 - Quantitative (R_{sh} range: 0.1 10000 Ohm)
 - High resolution (ca. 10 μm)
 - Metamaterial-based sensing
 - Increased sensitivity through near-field single element read-out
- Examples: THz device analysis
 - THz on-chip testing: Access to field vector components, amplitude, phase, time- & frequency domain information
 - Failure localization in chip packages: > 10-times increased fault location resolution through sub-ps rise-time THz signals



Contact information





Protemics GmbH

Otto-Blumenthal-Str. 25 D-52074 Aachen Germany www.protemics.com info@protemics.com Phone: +49 241 8867 140

Fax: +49 241 8867 140

